

L Number	Hits	Search Text	DB	Time stamp
-	1596	250/398	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 19:09
-	4216	250/492.2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:27
-	1003	250/492.21	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:27
-	798	250/492.22	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:27
-	351	250/492.23	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:27
-	75	250/492.24	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:27
-	2951	250/492.3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:27
-	2400	250/492.1	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:28
-	7567	430/5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:29
-	11291	(thin\$4 or thick\$4) near2 (mask or reticle)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:57
-	2	5831272.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:50
-	0	(Thicker or Thinner) Adj than NEAR2 (areas or portions or regions)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:20

-	0	((Thicker or Thinner) adj "than") NEAR2 (areas or portions or regions)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 18:57
-	1692	(Thicker or Thinner) NEAR4 (areas or portions or regions) NEAR4 (substrate or mask or reticle or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 19:01
-	83	((Thicker or Thinner) NEAR4 (areas or portions or regions) NEAR4 (substrate or mask or reticle or wafer)) and (250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 19:01
-	129	(Thicker or Thinner) NEAR2 (areas or portions or regions) NEAR2 (mask or reticle)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 19:02
-	2	6,327,022.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/04 19:10
-	26	((Thicker or Thinner) NEAR2 (areas or portions or regions) NEAR2 (mask or reticle)) and (250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/06 16:17
-	2	20020070354.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/06 16:22
-	42317	(Thicker or Thinner) NEAR4 (areas or portions or regions)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/06 18:40
-	1025	((plurality or multiple or many or numerous or (more adj than) or (at adj least)) WITH (substrate or mask or reticle or wafer)) WITH ((identical or "same") near3 (pattern))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/06 19:45
-	16337	250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/06 19:45
-	310	(250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5) and ((Thicker or Thinner) NEAR4 (areas or portions or regions))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/06 19:45
-	171	(250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5) and (((plurality or multiple or many or numerous or (more adj than) or (at adj least)) WITH (substrate or mask or reticle or wafer)) WITH ((identical or "same") near3 (pattern)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/06 19:45
-	34	((plurality or multiple or many or numerous or (more adj than) or (at adj least)) near2 (substrate or mask or reticle or wafer)) near2 ((identical or "same") near3 (pattern))) and (250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/06 19:53

-	2	5,006,795.pn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/04/06 20:38
-	351	(250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5) and ((Thicker or Thinner) NEAR4 (areas or portions or regions))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:12
-	1132	(250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5) and ((thin\$4 or thick\$4) near2 (mask or reticle))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:13
-	18027	(250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:18
-	139111	(plurality or multiple or many or numerous or (more adj than) or (at adj least)) NEAR4 (substrate or mask or reticle or wafer)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:21
-	201	((plurality or multiple or many or numerous or (more adj than) or (at adj least)) near2 (substrate or mask or reticle or wafer)) near2 ((identical or "same") near3 (pattern))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:22
-	557156	@pd>20030916	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:17
-	1169	@ad>20030916	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:17
-	557258	@pd>20030916 or @ad>20030916	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:17
-	768	((250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5) ) and (@pd>20030916 or @ad>20030916)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:18
-	6789	(Proximity NEAR3 (exposure or effect))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:21
-	83	((Proximity NEAR3 (exposure or effect)) ) and (((250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5) ) and (@pd>20030916 or @ad>20030916))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:21

-	49	((plurality or multiple or many or numerous or (more adj than) or (at adj least)) NEAR4 (substrate or mask or reticle or wafer)) and (((Proximity NEAR3 (exposure or effect)) ) and (((250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5) ) and (@pd>20030916 or @ad>20030916)) )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:21
-	1	((plurality or multiple or many or numerous or (more adj than) or (at adj least)) near2 (substrate or mask or reticle or wafer)) near2 (((identical or "same") near3 (pattern))) and (((Proximity NEAR3 (exposure or effect)) ) and (((250/398 or 250/492.2 or 250/492.21 or 250/492.22 or 250/492.23 or 250/492.24 or 250/492.3 or 250/492.1 or 430/5) ) and (@pd>20030916 or @ad>20030916)) )	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/12 10:22